





# Front-end Application Specific Integrated Circuits (ASICs) in 65 nm CMOS for Charge and Light Readout

**Prashansa Mukim**, Grzegorz Deptuch, Gabriella Carini, Hucheng Cheng, Shanshan Gao, Dominik Gorni, Jay Hyun Jo, Lingyun Ke, Steven Kettel, Soumyajit Mandal, Xin Qian, Sergio Rescia, Vladimir Tishchenko, Chao Zhang

November 8, 2023



# Status of Front-end ASICs



#### **3 ASICs vs. 1 ASIC solution:**

- Initially two readout options were proposed:
  - 3 ASICs vs. 1 ASIC (idea of building 1 ASIC, combining FE/ADC/transmission brought in 2016 and included as parallel path of development)
- Evolutionary development MiCroBooNE → DUNE led to the 3 ASIC solution that:
  - Helped perfect the FE (through multiple iterations)
  - Allowed debugging (procedure for ADC calibration)

Allowed optimization

Currently in development: <u>CHAMPS</u> (<u>CH</u>arge <u>AMP</u>lifer + <u>S</u>haper -> LArASIC translated to 65 nm + additional features)



# **Targets for CHAMPS**

Experiment	Temperature	Detector Capacitance	Shaping Time	Noise	Dynamic Range
DUNE FD 3/4 charge readout	89 K – 300 K	150 pF – 200 pF	250 ns – 2 μs	500 e <sup>-</sup> at 87 K	10 bits
nEXO light readout	160 K – 300 K	5 nF	1 µs	0.1 pe <sup>-</sup> at 160 K	10 bits
PIONEER	160 K – 300 K	20 pF	20 ns	570 e⁻ at 160 K	10 bits







# **Planned specifications**

#### LArASIC (P5B)

CHAMPS250 CHAMPS10

Technology	180 nm CMOS – 1-poly, 6-metal, MiM cap, sil blk resistors					
Supply Voltage	1.8 V					
Temperature Range	77 – 300 K					
Number of Channels	16					
Max Single-Ended Output Swing	1.4 V peak to peak (0.2 – 1.6 V)					
Gain Selection (mV/fC)	4.7	7.8	7.8		25	
Full-Scale Input Charge (fC)	300	180		100	56	
Baseline selection	200 mV (collection mode) 900 r			mV (induction mode)		
Charge Preamplifier Polarity	Negative (collection mode) Bipol			lar (in	ar (induction mode)	
Adaptive-Reset Current Selection (nA)	0.1	0.5		1	5	
Shaper Peaking Time Selection (µs)	0.5	1		2	3	
Output Coupling	AC (100 µs HPF time-constant) DC					
Output Selection	Shaper SE buffer			SEDC buffer		
Total Channel Settings	1024					
Integrated Test Capacitor	200 fF					
Temperature Sensor	0.8728 V @ 25°C + 2.868 mV/°C					
Integrated Pulse Generator	6-bit DAC based					
Configuration Control	SPI interface with 144 register bits					

65 nm CMOS: 1-poly, 9-metal	65 nm CMOS: 1-poly, 9-metal
$\checkmark$	✓
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$\checkmark$	✓
$\checkmark$	$\checkmark$
$\checkmark$	✓
$\checkmark$	✓
$\checkmark$	✓
250 ns – 2 μs	10 ns – 250 ns
$\checkmark$	✓
$\checkmark$	✓
TBD	TBD
TBD	TBD
$\checkmark$	✓
$\checkmark$	$\checkmark$
I <sup>2</sup> C interface	I <sup>2</sup> C interface



# LArASIC – status

LArASIC MPW met all the DUNE requirements → fabricated ~1800 P5 and 1800 P5B (180 nm) chips (eng. run) for ProtoDUNE II

LArASIC Chips	Temp.	Tested Chips#	Good # (All channels are normal)	Yield
P5	RT	49	49	100 %
P5B	RT	1642	1635*	~99.57 %
P5B	LNT	317	317	100 %

P5B has improved input ESD protection compared to P5

\*Only 1 out of 16 channels in each of the two chips are non-functional >6 months ago, now more statistics is available



LArASIC performance with differential interface





250 wafers LArASIC production run for DUNE 75k P5 and 75k P5B chips

8" wafer with 610 LArASICs P5 and P5A(B) w. increased ESD protection



24 FEMBs arrived at CERN for ProtoDUNE-II installation

# **Measured characteristics (LArASIC P5)**





# **Measured characteristics (LArASIC P5)**





#### **CHAMPS status & overview**



### **Circuit implementation**



Schematic level design in 65 nm completed with 3 mW power consumption and programmable shaping times of 250 ns, 500 ns, 1 µs and 2 µs



# **Charge Sensitive Amplifier design**



- Charge amplifiers use current-mirror based adaptive continuous reset
- A<sub>1</sub> and A<sub>2</sub>: 3-stage amplifiers (> 100 dB gain each, bandwidths of 10 MHz and 20-50 MHz)
- Pole zero cancellation ( $C_f R_f = C_z R_z$ ) ensures fast  $I_{csa1}$  pulse and prevents baseline drift

$$I_{csa1}(s) = \underbrace{I_{in}(s) \frac{R_{f1}}{(1 + sC_{f1}R_{f1})} \frac{(1 + sC_{z1}R_{z1})}{R_{z1}}}_{V_{csa1}}$$

- $C_{z1} = 20C_{f1}$ ,  $R_{z1} = (1/20)R_{f1}$ , charge gain provided by  $CSA_1 = 20$
- $C_{z1} = (3 \text{ or } 5 \text{ or } 9 \text{ or } 16)C_{f1}$ ,  $R_{z1} = (1/3 \text{ or } 1/5 \text{ or } 1/9 \text{ or } 1/20)R_{f1}$ , charge gain (programmable) provided by  $CSA_2 = 3 \text{ or } 5 \text{ or } 9 \text{ or } 16$

### CSA<sub>1</sub> and CSA<sub>2</sub> charge multiplication check



### **CSA<sub>2</sub> reset current subtraction**



- Reset Quiescent Current (RQI) subtraction for CSA<sub>2</sub> to be implemented in CHAMPS
- Prevents propagation of leakage current and corresponding baseline shift
- To be made programmable (2-3 bits) with digital assistance independently for each channel
- Suitable for applications that have high leakage current and involve DC coupling



# Shaper design



$$V_{s1}(s) = I_{csa2}(s) \frac{R_1}{(1 + sC_1R_1)}$$

$$V_{s2}(s) = V_{s1}(s) \frac{\frac{1}{R_{21}R_{41}C_{21}C_{31}}}{s^2 + s\left(\frac{1}{R_{21}C_{21}} + \frac{1}{R_{31}C_{31}} + \frac{1}{R_{41}C_{21}}\right) + \frac{1}{R_{31}R_{41}C_{21}C_{31}}}$$

Brookhaven National Laboratory

$$V_{s3}(s)$$
 is similar....

- Implemented shaper is a 5<sup>th</sup> order semi-gaussian filter with complex conjugate poles
- V<sub>csa2</sub> output is a fast pulse, poses stringent requirements on peak capturing circuit (must be fast and accurate)
- Shaper slows down the variations near signal peak
- (Nearly) equal rise and fall times maximize the output signal amplitude for a given pulse duration



S. Ohkawa, M. Yoshizawa, K. Husimi, 13 Direct synthesis of the Gaussian filter for nuclear pulse amplifiers.

### **Noise minimization strategy**

$$ENC^{2} = (C_{d} + C_{in})^{2} \left(A_{w} v_{n}^{2} \frac{1}{T_{p}} + A_{f} K_{f}\right) + A_{p} i_{n}^{2} T_{p}$$

(Sum of white series noise, 1/f series noise and parallel noise components)

Input stage transistors for A<sub>1</sub> implemented using thick oxide (2.5 V) devices in 65 nm to limit leakage current and associated parallel noise

$$ENC_f^2 = K_f \frac{(C_d + C_g)^2}{C_g} N_f \Rightarrow C_g = C_d$$
$$ENC_w^2 = 4k_B Tn\gamma \alpha_w \frac{(C_d + C_g)^2}{g_m(C_g)} N_f \Rightarrow C_g = \frac{1}{3}C_d$$

Input stage transistor sized to have  $C_g \sim 40 \text{ pF}$ , optimal choice for minimizing noise with  $C_{det} \sim 150 \text{ pF}$  with given power budget

	Minimum allowable transistor length	Input transistor length	Input transistor width
180 nm	180 nm	270 nm	20 mm
65 nm	280 nm	400 nm	24 mm

Noise in 65 nm (simulated) about 10 % lower than 180 nm



#### **Transient responses**

Variable charge gain (3, 5, 9, 16)

#### Variable peaking time (250 ns, 500 ns, 1 µs, 2 µs)





# **Linearity characteristics**

Name

Shaper response for charge gain = 3,  $T_p = 1 \ \mu s$ 



#### **Output amplitude Vs. input charge**





# Plan for CHAMPS10 ( 10 ns $\leq T_p \leq 250$ ns)



- Limited bandwidth of A<sub>1</sub> and A<sub>2</sub> disallows shaping times < 250 ns</li>
- Currently, amplifiers A<sub>1</sub> and A<sub>2</sub> implemented as 3-stage amplifiers
- Difficult to achieve higher bandwidth without sacrificing stability
- CHAMPS10 will incorporate topology modification for  $A_1 \mbox{ and } A_2$

Transient response for variable input charge (50 fC -300 fC) with A<sub>1</sub>, A<sub>2</sub>, A<sub>3</sub> modeled as ideal VCVS





# Thank you

